Carbon coating technology

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1. Introduction to a-C films with low Secondary Electron Emission

Secondary Electron Yield (SEY, δ) of carbon materials Effect of Impurities Ageing in air Ageing

2. Coating technology at CERN

Coating techniques Adapt the coating technique to the constrains The SPS case The HL-LHC case

3. Summary



TRIUMF 2021 EIC Accelerator Partnership Workshop

EIC2021 Accelerator Partnership Workshop

The SEY (δ) of carbon materials depend on the molecular bonds between carbon atoms.





The effect of impurities: hydrogen is bad



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The effect of impurities: hydrogen is bad nitrogen is good



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Ageing



Figure 1 Evolution of the SEY maximum in a relation of storage time in Al foil for different samples prepared without hydrogen addition into the discharge.



Ageing



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Coating techniques













Adapt the coating technique to the constrains

- Geometry of the object to be coated: cylindrical, planar, ellipsoidal, etc.
- Accessibility: tube with/without flanges; already inserted in a yoke of a magnet; in the accelerator tunnel;
- □ Adhesion: substrate material, surface treatments, bakeout before coating?
- Residual gas during coating: outgassing / pumping (materials; bakeout before coating? thermal treatments)
- □ Schedule & budget

□ Whenever possible, integrate the coating process from the design phase.



The SPS case



Quad and dipole chambers are embedded in the yoke. (bakeout not possible)

Keep quads and dipoles in the ring => coat *in-situ*















The SPS case

Quad chambers Ellipsoid

QF quads



Coat in-situ by DC hollow cathode sputtering

MBB dipoles

Dipole chambers racetrack







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The SPS case

Quad chambers Ellipsoid





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MBB dipoles



No bakeout before coating Pressure Ar ~1.1x10⁻¹ mbar Power density ~ 120 W / m Sputtering rate ~ 20 nm / hour 20 hours -> 400 nm films

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The SPS case

The first large scale production in the SPS during the CERN Long Shutdown (**212 coating runs**):

88 QF quadrupole magnets (294 m) coated in-situ 2 runs / week with 2 systems

110 Short straight Section elements (104 m) coated ex-situ 2 runs / week with 2 systems

29 Drift vacuum chamber (80 m) coated ex-situ 2 runs / week with 2 systems



Histogram of the SEY_{max} for the whole LS2 coating campaign



The HL-LHC case

In-situ coatings (inner triplets ALICE and LHCb)



Ex-situ coatings (New inner triplets ATLAS and CMS)





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The HL-LHC case

In-situ coatings (inner triplets ALICE and LHCb)



Only 150 mm to insert the coating device => modular sputtering source

High outgassing of H_2O and $H_2 => Ti$ gettering



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The HL-LHC case

In-situ coatings (inner triplets ALICE and LHCb)

Pulled by cables along the beam screen



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High outgassing of H_2O and $H_2 => Ti$ gettering

Cu substrate => critical for adhesion => ion etching + Ti underlayer



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The HL-LHC case

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3 weeks to coat a 14 m long quad => several systems in parallel

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The HL-LHC case

In-situ coatings (inner triplets ALICE and LHCb)





The HL-LHC case

Ex-situ coatings (New inner triplets ATLAS and CMS)

=> Adapt the in-situ technology to the new geometry









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The HL-LHC case

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The a-C film resisted to the deformations induced by quenching at nominal currents.

Tests at 4x nominal current ongoing.



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The HL-LHC case

Optical inspection devices (before / after coating)



Raspbery Pi camera + motherboard + battery + LED based light system



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3 – Summary

- The coating technique to produce carbon films with low SEY must favor sp2 hybridization (sputtering, PLD). SEY increases with H content and decreases with N content.
- A growing technological *corpus* is available to cope with the constrains of the particle accelerator's community: in-situ / ex-situ; getter co-deposition; N doping; re-set of copper oxide; optical inspection devices...
- Large scale production is feasible: more than 200 coating runs during the LS2 coating campaign in the SPS resulted on a average SEY ~1. (in-situ + ex-situ coatings). More to come during LHC run 3 (exsitu) and LS3 (in-situ).
- No pre-defined recipe: the coating technique & process should be adapted to each specific case. Take into account the coating from the design phase is the bet practice.







